



## [ThE1] CMP for Heterogeneous Integration and New Materials

<b>Session Date</b>	November 13 (Thu.), 2025
<b>Session Time</b>	09:00-10:45
<b>Session Room</b>	Room E (Sicily Room, 1F)
<b>Session Chair</b>	Prof. Kangchun Lee (Kwangwoon Univ., Korea)

### [ThE1-1] [Plenary]

09:00-09:45

#### Role of CMP in Enabling New Materials for Heterogeneous Integration

K. Mikhaylichenko, C. Lee, T. Osterheld, S. Barkam, S. Deshpande, B. Brown, R. Sreenivasan, S. Krishnan, M. Khoury, J. Lei, Z. Chen, K. Sharma, B. Chen, and V. Sukumaran (Applied Materials, USA)

### [ThE1-2] [Invited]

09:45-10:15

#### Oxide Layer Engineering for Cobalt CMP

Taeseup Song, Ungyu Paik, Ganggyu Lee, Sumin Hong, and Giha Lee (Hanyang Univ., Korea)

### [ThE1-3] [Invited]

10:15-10:45

#### Hybrid Bonding Challenges and Advanced CMP Strategies for Yield Enhancement

Haeri Kim, Hyeok Joo Lee, Sangchul Kim, and Jong Han Shin (SK hynix Inc., Korea)